

PATENT APPLICATION
IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Docket No: Q80214

Tsutomu SHOKI , et al.

Appln. No.: Not yet assigned

Confirmation No.: Not yet assigned

Group Art Unit: Not yet assigned

Filed: March 02, 2003

Examiner: Not yet assigned

For: REFLECTIVE MASK BLANK HAVING A PROGRAMMED DEFECT AND
METHOD OF PRODUCING THE SAME, REFLECTIVE MASK HAVING A
PROGRAMMED DEFECT AND METHOD OF PRODUCING THE SAME, AND
SUBSTRATE FOR USE IN PRODUCING THE REFLECTIVE MASK BLANK OR
THE REFLECTIVE MASK HAVING A PROGRAMMED DEFECT

PRELIMINARY AMENDMENT

MAIL STOP NON-FEE AMENDMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

Prior to examination, please amend the above-identified application as follows on the
accompanying pages.

TABLE OF CONTENTS

AMENDMENTS TO THE CLAIMS	2
REMARKS	6